Biweekly GBP meeting

Frascati data analysis





15/06/2022 | P. Grutta - Biweekly GBP meeting

Frascati test beam

Status of the analysis

Few points to account

- 1. MC estimate to be improved (~ 30%)
 - Detailed geometry
 - Beam misalignment and/or profile smearing
- 2. Data points must be corrected (min<CH>, 8-bit, pickup noise) (<15%)
- 3. Fit model must be revised
- 4. Allpix² simulation for the charge collected

Current status

MC improved with all the details of the geometry. Data biasing (min<CH>, 8-bit) studied in detail and error constrained to 15%. Analysis of the BTF data ongoing, data correction to be accounted yet. Fit model worked out in the general case of uniform initial charge distribution, moving in an arbitrary $E(z) = E_0 + E_1 z + E_2 z^2$ field; implementation of the fit model in ROOT ongoing.

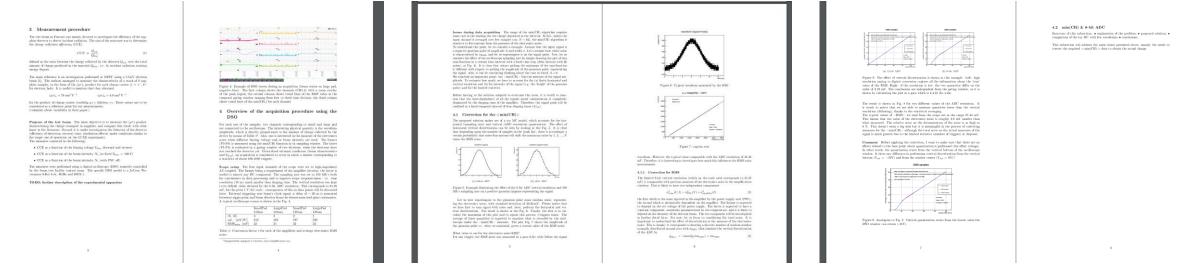
Status of the analysis

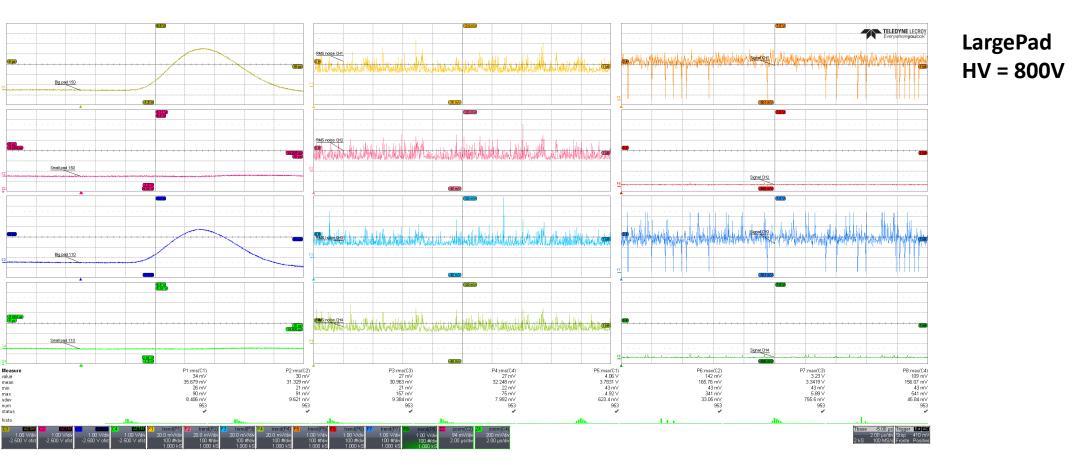
Few points to account

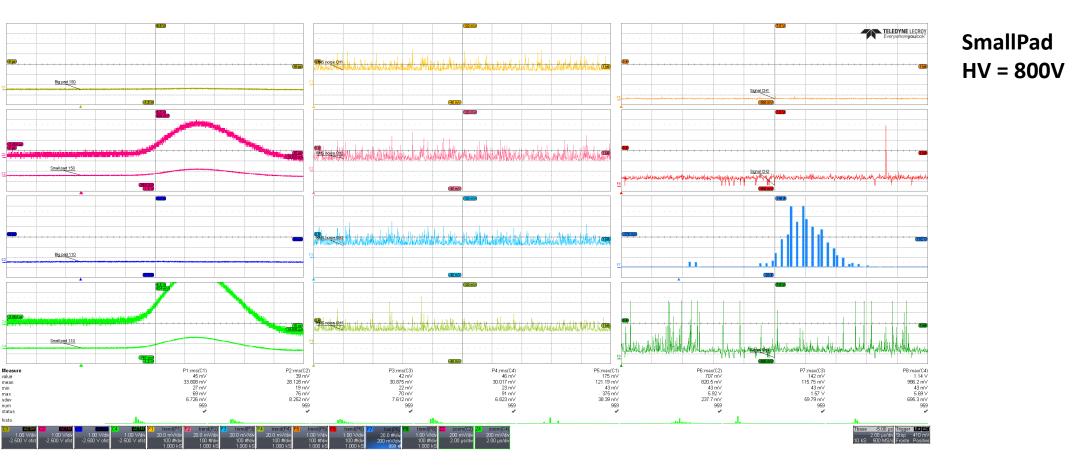
- ✓ MC estimate improved (~ 30%)
 - Detailed geometry
 - Beam misalignment and/or profile smearing
- ✓ Data points corrected (min<CH>, 8-bit, pickup noise) (<15%)</p>
- ✓ Fit model must be revised
- Solution ≤ Allpix² simulation for the charge collected

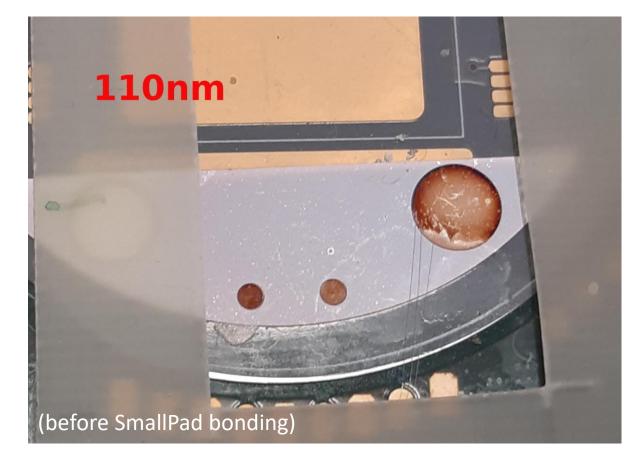
Current status

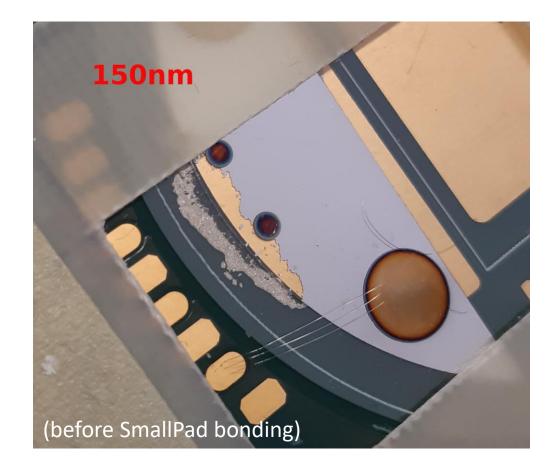
MC improved with all the details of the geometry. Data biasing (min<CH>, 8-bit) studied in detail and error constrained to 15%. Data corrections accounted. Analysis of the BTF data completed. Fit model worked out in the general case of uniform initial charge distribution. Fit results for uniform E in the next slides. Allpix² simulation under development. Mostly accounted to fix the bias we introduced when measuring the signal using the <min(CH)> function. More details will be available in a report of the Frascati testbeam I'm writing











- 3. Charge multiplicity has been corrected using recorded average data by the lead-glass calorimeter (BTF data).
- 4. Beam characteristics (sigma X, sigmaY) variations have been accounted in the estimate of deposited charge.

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| 28 | | 1452 389 30.06 26.58 1455 509 31.12 27.98 | 119 Carica depositata da MC con fascio allineato perfettamente al pad piccolo/grande e sigma (xx, sy) mm 120 filename Sigma fascio X (mm/Sigma fascio Y (mm/Sigma gun X Sigma gun Y (mm) charge triggers pad edep110 stodev e dep151 stodev edep150 |
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| 31 | | | 122 X0 Y0 5X2 2.14 1.60 1.96978 1.38828 50 977 YP 20.17 1.11 27.19 1.42 123 X0 Y0 5X2 2.14 1.65 1.96978 1.44213 504 832 YP 20.09 1.11 27.02 1.38 |
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| 39 Reverse bias | | | 131 X0_Y0_5X2 2.13 1.88 1.95901 1.68980 1016 959 5P' 4.75 0.67 6.28 0.85 |
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| 47 48 | Chart Area | | 139 140 |
| 49 Punti extra | | | 141 |
| 50 1000 1038 scarica 100 | 00 1056 | | 142 <min(ch)> correction</min(ch)> |
| 52 | | | 143 Correzione da <min(ch)> ad ampiezza segnale 144 Reverse Vbias measures</min(ch)> |
| 53 Risultati fit (veloce) 54 Small pad | rev bias signal vs vbias (small pad) | Risultati fit (veloce) Small pad | 145 Reverse volas measures 145 De AMS- disc. to the AMS |
| 55 Slope 110 Slope 110 err. 1200.0 | | Slope 110 Slope 110 err. | 6000.0 146 Linear regression parameter for the <rms> (you enter the value of undiscretized value of <rms> and read the one that is returned by the DSO)</rms></rms> |
| 56 1.254857 0.150876983 | | 4.062 0.1920093 | 5000 147 m q [mV] 5000 148 0.65192 2.3832 |
| 57 Constant 1 Const. 110 err. 1000.0 58 -104.762 91.36055009 800.0 | • | Constant 110 Const. 110 err. -20 116.2674053 | 149 |
| 59 Slope 150 Slope 150 err. | • | Slope 150 Slope 150 err. | 4000 150 Smillad Unear regression parameters for cmax(CH) (you enter the cmax 151 Friggers SmallPad 150 noise SmallPad 150 true [mV] RMS [mV] m q (mV) SmallPad 110 millad 110 true [mV] |
| 60 0.957857 0.031073755 600.0 61 Constant 1 Const. 150 err. | | 4.356 0.188458155 Constant 150 Const. 150 err. | analisi analisi_oldMinCH analisi_oldMC dati_scantavolo dati_vbias_dati_intensità analisi_RMS analisi_oldCal dati_vbias_oldMC |
| 62 -12.7619 18.81609289 400.0 | | 78.3333333 114.11708 | 2000.0 Ready 🛱 Accessibility: Investigate |
| 63 Slope ratio 200.0 64 150/110 150/110 err. | | Slope ratio | 1000.0 |
| 65 0.7633 1.17E-01 0.0 | | 150/110 150/110 err. 1.0724 9.71E-02 | |
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Fit model

CCEAvgE[
$$k_{-}$$
, V_{-}] := Abs $\left[k V \left(1 - k V \left(\text{Exp}\left[\frac{1}{k V}\right] - 1\right)\right)\right]$;
CCEAvgH[k_{-} , V_{-}] := Abs $\left[k V \left(1 - k V \left(1 - \text{Exp}\left[-\frac{1}{k V}\right]\right)\right)\right]$;
Hecht[k_{-} , V_{-}] := Abs $\left[k V \left(1 - \text{Exp}\left[\frac{1}{k V}\right]\right)\right]$;

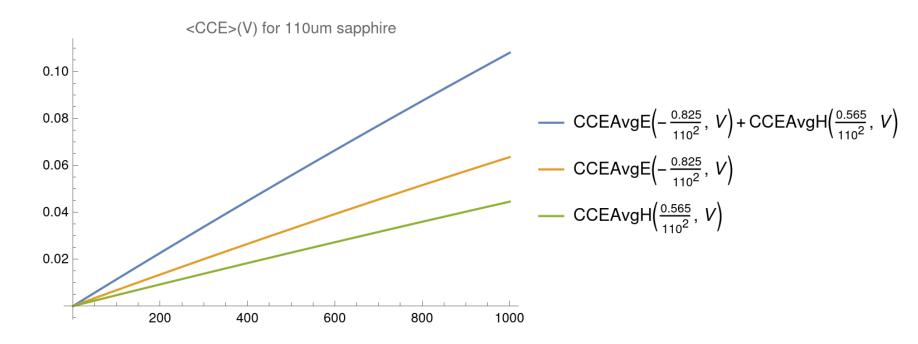
Energy deposited uniformly over thickness d^(MIP) Carriers generation (Q= E / 27eV) Propagation in uniform field E=V/d

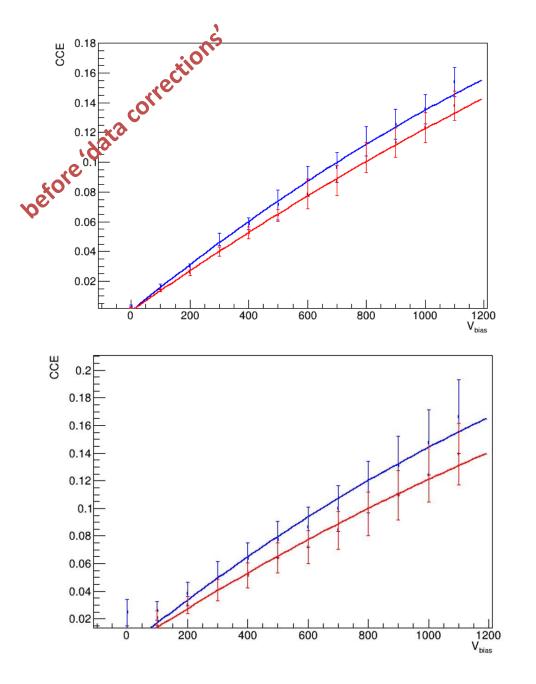
Problem

The hole contribution cannot be clearly distinguished from the electron one.

Fitting data, by assuming hole's contribution is negligible, can give an idea of the (\mu\tau)_e product.

Comparison with both alpha experiments parameter and literature can be useful to test the Hecht assumptions for the internal field.





2.Fitting <CCE(V)> Forward bias

LargePad

110 um wafer

before data corrections Giving for the mutau product: 1.94 +/- 0.05 um2/V

150 um wafer

Giving for the mutau product: 3.16 +/- 0.08 um2/V

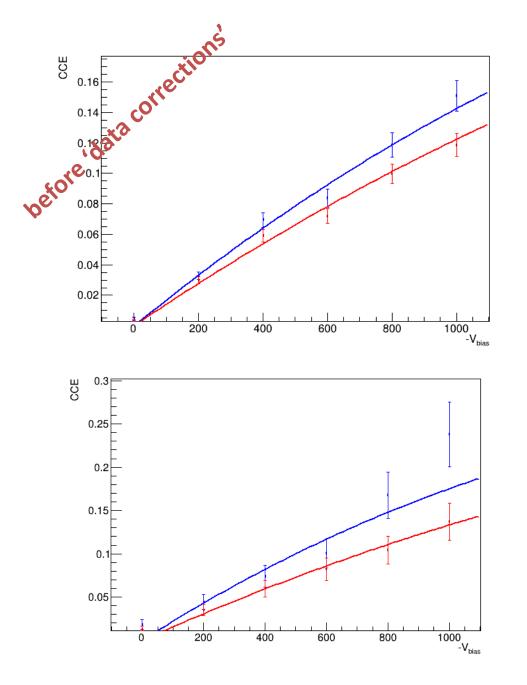
SmallPad

110 um wafer

Giving for the mutau product: 2.11 +/- 0.13 um2/V

150 um wafer

Giving for the mutau product: 3.2 +/- 0.2 um2/V



2.Fitting <CCE(V)> **Reverse** bias

LargePad

110 um wafer

before data corrections Giving for the mutau product: 2.08 +/- 0.07 um2/V

150 um wafer

Giving for the mutau product: 3.22 +/- 0.11 um2/V

SmallPad

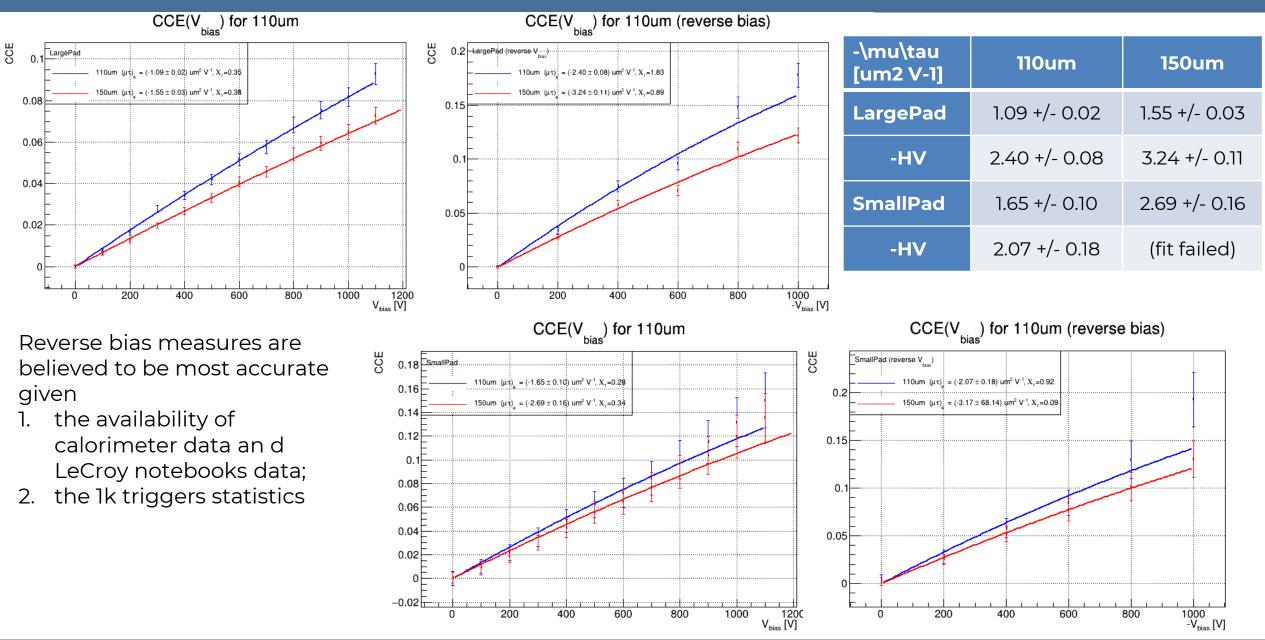
110 um wafer

Giving for the mutau product: 2.7 +/- 0.2 um2/V

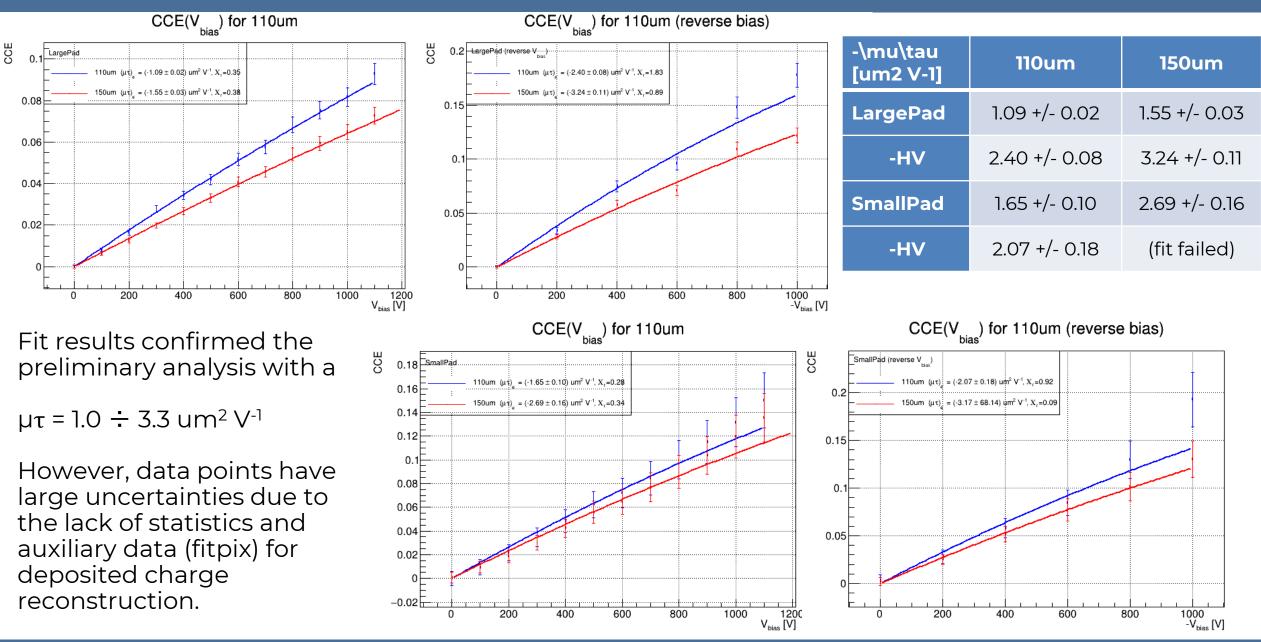
150 um wafer

Giving for the mutau product: 3.3 +/- 0.3 um2/V

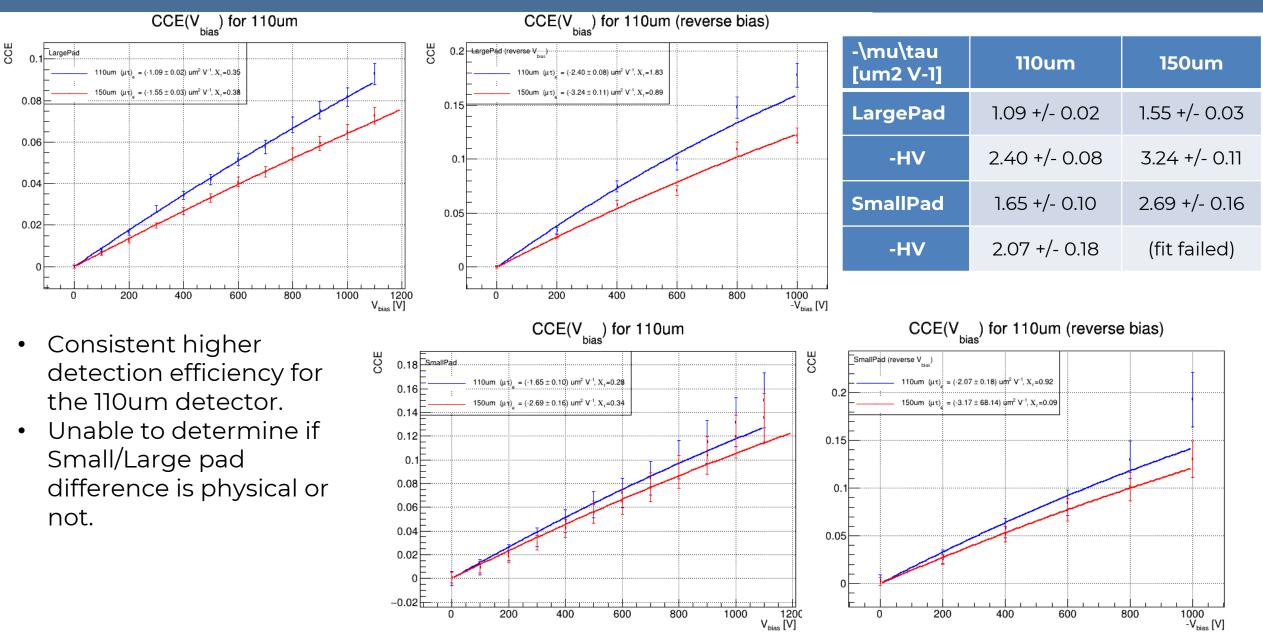
Fit results



Fit results



Fit results



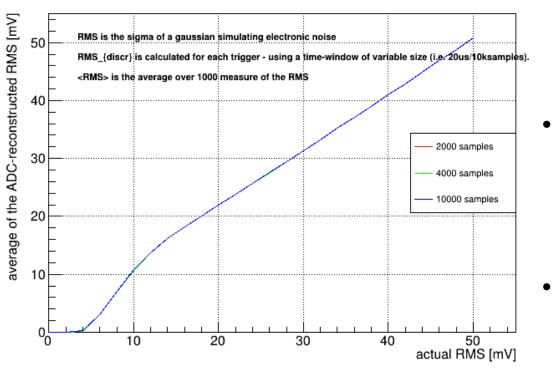
backup

DSO ADC resolution

| C1 C2 ACIMI 1.00 ∨/div C3 -2.500 ∨ ofst -2.500 ∨ ofst -2 | | | | | | | | |
|---|------------|-----------|------------|------------|-------------|------------|----------|-----------|
| | | | | | | | | |
| Cursors | X1 | X2 | DeltaX | Y1@X1 | Y2@X2 | DeltaY | Y3 | Y4 |
| value | 7.5249 µs | 7.6912 μs | 166.3 ns | 226 mV | 242 mV | 16 mV | 275.1 mV | 224.7 mV |
| Measurements | Amplitude | Μax | Mean | Min | Area | Base | Top | Rms |
| value | 133 mV | 275 mV | 220 mV | 142 mV | 209.020 nWb | 142 mV | 275 mV | 221 mV |
| Measurements | Delay | Duty | Fall 90-10 | Fall 80-20 | Rise 10-90 | Rise 20-80 | Period | Frequency |
| value | 7.44801 µs | 85.000 % | 364.80 ns | 363.61 ns | 19.20 ns | 18.40 ns | 40.00 ns | 25.00 MHz |

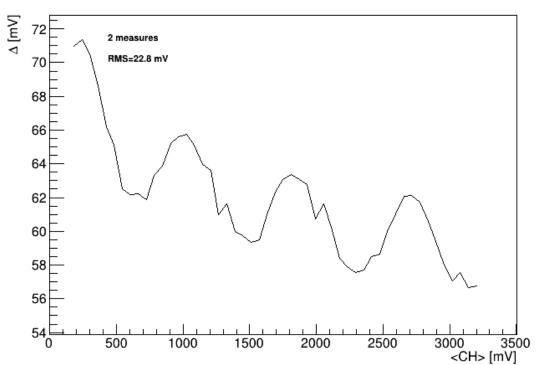
This matter for the measurement of

- the electronic noise
- the signal, which we measured using <min(CH)> and which is a function of f(<min(CH)>)



- Assume that the electronics noise is completely randomic, and it's normally distributed with a certain sigma ('actual RMS').
- This noise overlays the actual signal, and this waveform is then fed in the DSO front-end where the analog signal is quantized over the 8-bit resolution (31.25 mV)
- Dithering from signal+noise sampling make the measure of the RMS noise meaningful, as illustrated here

The Fig. shows that if we read $\langle RMS \rangle = 32 \text{ mV} - e.g.$ the RMS is calculated in a 2k sample window (2us) and the average over 1k triggers – the true unbiased RMS value is 32 - 2.67 = 29.3 mV.



 $\Delta \equiv <\mathsf{max}(\mathsf{CH}) > - <\mathsf{CH} >$

- Incidentally, this toy model shows that dithering allows to measure the <RMS> noise with a precision smaller than the ADC resolution.
- However, to the pure electronics noise we have to add another noise distrubing the signal measure: the noise from the environment
 - Waveforms (right)
 - Trace of RMS noise (left)

The difference Δ depends from the intensity of the <CH> itself, given that the sampling rate is fixed and the shaping time determines the temporal width of the peak.